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6036929A2: PLATED MAGNETIC THIN ILM AND MANUFACTURE THEREOF

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Country

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Issued/Filed Dates:

Feb. 10, 1994 / July 17, 1992

Application Number

JP1992000191034

PC Class H01F 10/16; C25D 3/56; C25D 5/26; H01F 41/26;

Abstract: Purpose: To realize a plated magnetic thin film, which has a low coercive force, a high saturation magnetic flux density and a high corrosion resistance, by a wet plating method which is superior in mass productivity.

Constitution: A magnetic thin film has the content of Sn of 8 to 25wt.% in a Co-Fe-Sn alloy film; which is formed by a plating method. A film is formed by an intermittent current and the plated magnetic thin film is manufactured in the maximum current density of three amperes/dm2 or higher, in a current conduction time Ton of one pulse of 0.05 to 2 seconds and in the ratio of current conduction time Ton/(current conduction time Ton + down time Toff)=1/0.15 to 0.5. Thereby, the soft magnetic characteristics of the plated magnetic thin film is superior and the corrosion resistance of the plated magnetic thin film is also improved.

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Other Abstract Info

CHEMABS 120(22)288297U CAN120(22)288297U DERABS C94-087048 DERC94-087048

Foreign References:

(No patents reference this one)

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IBM Technical Disclosure Bulletin